

Serial No.: To Be Assigned  
Filing Date: May 12, 2005

Dear Sir:

Preliminary to the examination of the above-mentioned application, please  
add new claim 4-12:

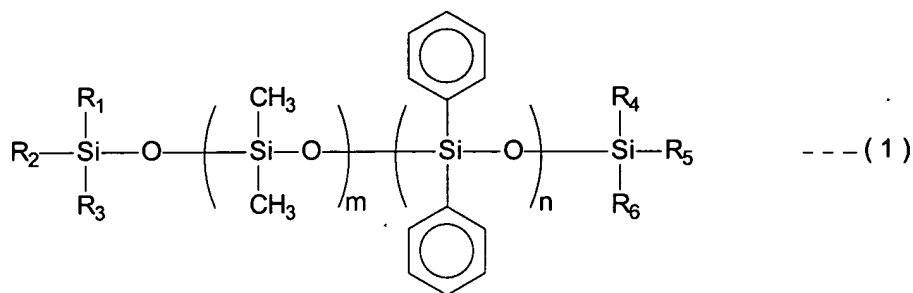
**Amendment to the Claims** are presented on page 2 of this paper.

**Remarks** are on page 5 of this paper.

EXPRESS MAIL MAILING LABEL NO. EV 540353490 US

**Complete set of claims**

1(original). An application property-improving agent for a photosensitive resin composition, comprising a poly(dimethylsiloxane-diphenylsiloxane) copolymer silicone oil represented by the general formula (1):



wherein R<sub>1</sub>, R<sub>2</sub>, R<sub>3</sub>, R<sub>4</sub>, R<sub>5</sub> and R<sub>6</sub> independently represent a hydrogen atom, a hydroxyl group, a C<sub>1-4</sub> alkyl group or an aryl group, m is an integer of 1 to 40, and n is an integer of 1 to 40.

2(original). A photosensitive resin composition comprising an alkali-soluble resin and a photosensitizer, wherein the photosensitive resin composition comprises a poly(dimethylsiloxane-diphenylsiloxane) copolymer silicone oil represented by the general formula (1) in claim 1.

3(original). The photosensitive resin composition according to claim 2, wherein the alkali-soluble resin is a novolak resin, and the photosensitizer is a compound having a quinonediazide group.

4(new). A process for imaging a photosensitive composition comprising the steps of,

a) forming a coating of a photosensitive composition from claim 2 on a substrate;

b) imagewise exposing the photosensitive composition ; and

d) developing the coating with an alkali developing solution.

5(new). The process of claim 4, where the substrate is glass.

6(new). The process of claim 5, where the substrate has a coating.

7(new). The process of claim 6, where the coating is chrome.

8(new). The process of claim 4, where the substrate is silicon.

9(new). The process of claim 8, where the substrate has a coating.

10(new). The process of claim 9, where the coating is silicon oxide.

11(new). The process of claim 4, where the developing solution is an aqueous solution.

12.(new) The process of claim 4, where the developing solution is an aqueous solution selected from tetraalkyl ammonium hydroxides, choline, alkali metal hydroxides, alkali metal metasilicates, alkali metal phosphates, ammonia water, alkylamine, alkanolamine and heterocyclic amines.